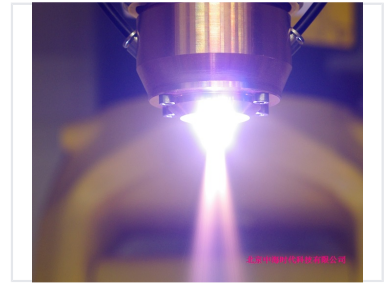


Plasma Coating System for Thin Film Deposition

This plasma coating system is designed for applying thin films and coatings onto various materials. It uses plasma to deposit materials with exceptional adhesion and control over film properties.

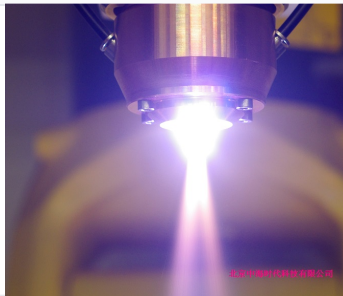


Overview

Advanced Plasma Coating Technology

This plasma coating system is a sophisticated device designed for high-precision surface modification and thin film deposition. By utilizing a high-energy plasma jet, the system enables the targeted feeding of powders and precursors to create dense, compact coatings without the use of solvents. It is engineered for versatility, supporting both micro-layer and nano-layer applications across a wide variety of substrates.

Technical Specifications



The core of the system features a precision nozzle assembly for targeted feeding of powder and precursor into the plasma jet.

Supported Coating Types

- Cleaning and activation of substrate
- Micro layers (Zinc, Tin, Copper, etc.)
- Nano layers

Micro Layer Thickness	500 μ m
Nano Layer Thickness	300 nm

Process Capabilities

Core Process Metrics

1000 °C

Plasma Jet Temperature

Atmospheric Pressure Processing	Yes
Coating Characteristics	Dense, Compact, Solvent-free, High-speed